

HVR_CCPD and CHPIX65 chip design – Milano

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DI MILANO

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- 1 Introduction
- 2 Radiation Hardening Approach
- 3 CHIPIX65: DICE SRAM
- 4 CHIPIX65: D2RA (Double-Rail Redundant Approach) Logic
- 5 HVR_CCPD: High-Voltage/High-Resistivity Capacitively Coupled Pixel Detector
- 6 Conclusion

INFN-Milano design team:

Valentino Liberali, Alberto Stabile, Seyedruhollah Shojaii (chip design);
Mauro Citterio, Alessandro Andreani, Fabio Manca (PCB and chip assembling);
Alessandra Camplani (FPGA firmware and radiation tests);
Attilio Andreazza, Chiara Meroni, Francesco Ragusa (pixels)

Collaboration with Hitesh Shrimali, Indian institute of Technology, Mandi, India.

The Associative Memory chip (AMchip) for FTK

Since 2010, INFN-Milano is involved in the design of the **Associative Memory chip for the Fast Tracker (FTK) project in ATLAS**, using TSMC 65 nm CMOS technology

Several versions of the AMchip:



<i>Vers.</i>	<i>Design</i>	<i>Tech.</i>	<i>Area</i>	<i>Patterns</i>	<i>Package</i>
4	Std cells + Full custom	65 nm	14 mm ²	8 k	QFP
mini-5	Std cells + Full custom	65 nm	4 mm ²	0,5 k	QFP
5	+ SERDES IP blocks		12 mm ²	3 k	BGA
6	Std cells + Full custom + SERDES IP blocks	65 nm	160 mm ²	128 k	BGA

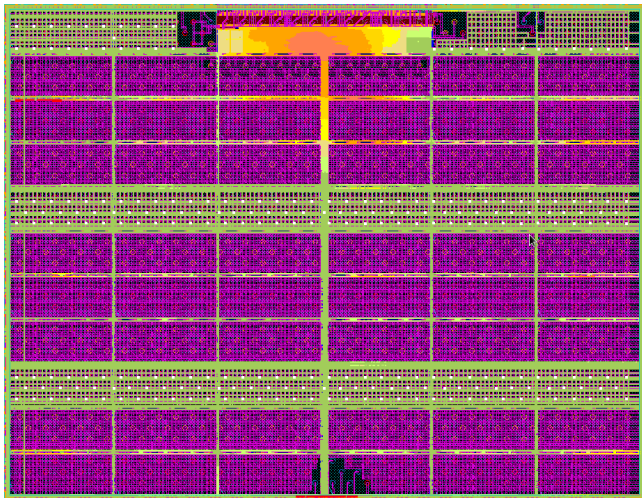
blue = under design

AMchip06

Last version: **AMchip06**

168 mm², 421 M transistors

Floorplan:



Design of large IC's with Cadence Encounter
Mixed approach (full-custom, standard cells, IP blocks)
Use of timing analysis tools (Tempus) and *IR* drop analysis tools (Voltus)

The screenshot displays the Altium Designer software interface. The top menu bar includes 'Applications', 'Places', 'System', and various toolbars. The main workspace shows a PCB layout with a color-coded signal integrity analysis. The right-hand panel is titled 'Power & Rail Results' and is currently showing the 'Advanced' tab. This panel contains a table of results for various power planes, including columns for 'Plane', 'Count', and 'Units'. The table lists several power planes with their respective counts and units. Below the table, there are sections for 'Filter Info' and 'Filter Filter', which allow users to filter the results based on various criteria. The bottom status bar shows the current file name and the active window.

Radiation Hardening Approach

Within RD53/CHIPX65:

Digital IP blocks designed in 65 nm CMOS technology (TSMC) using RHBD (Radiation Hardening By Design) techniques.

REDUNDANCY technique has been used for:

- DICE SRAM
 - Array of 256×256 cells designed with three different layouts
 - Prototypes available
 - Test board designed
 - Test firmware under development
 - Radiation test planned in July
- D2RA logic
 - New logic family based on redundancy: each signal is propagated on two wires (bit and inverted bit)
 - Cells designed
 - Test chip under design; MPW submitted in May

Scopo e partecipanti

Scopo: Lo sviluppo di un pixel chip innovativo in tecnologia CMOS 65nm (TSMC) resistente a altissimi flussi di particelle e radiazione si inserisce nella partecipazione italiana al progetto CERN RD53, di cui CHIP65 è parte.

A RD53 (e a CHIP65) partecipano unità coinvolte nei progetti ATLAS e CMS. L'obiettivo finale è il progetto di un sensore a pixel, con relativa elettronica, adatto per la fase II di LHC.

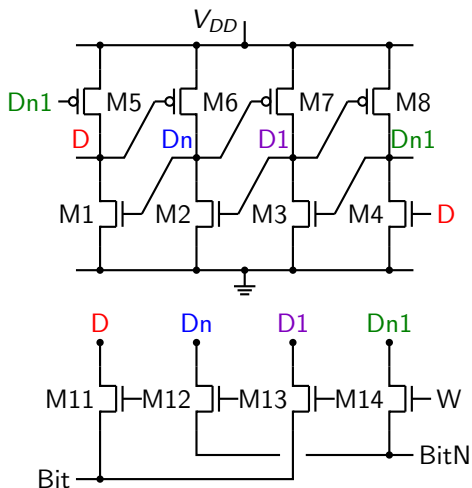
Coordinatore: **N. Demaria (Torino)**

Unità partecipanti: **Bari (CMS), Bergamo + Pavia (CMS), Milano (ATLAS), Padova (CMS), Perugia (CMS), Pisa (CMS + ATLAS), Torino (CMS)**

Partecipazione di Milano: **1 FTE**

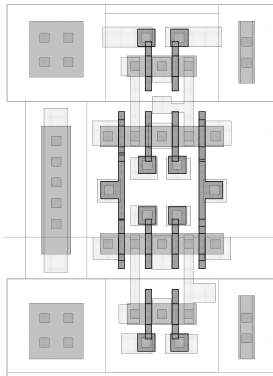
Valentino Liberali, Seyeduhollah Shojaii, Alberto Stabile

DICE (Dual Interlocked CEII) SRAM: schematic



T. Calin, M. Nicolaidis, and R. Velazco, "Upset hardened memory design for submicron CMOS technology," *IEEE Trans. Nucl. Sci.*, vol. 43, pp. 2874-2878, Dec. 1996.

DICE (Dual Interlocked Cell) SRAM: layout

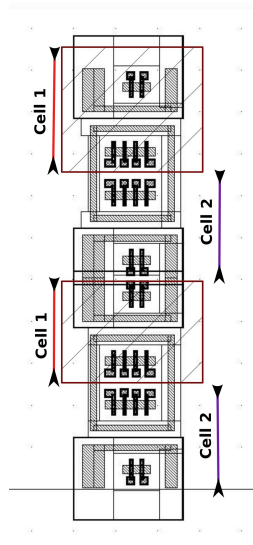


Simple layout

Minimum transistor size:
 $W = 200 \text{ nm}$, $L = 60 \text{ nm}$

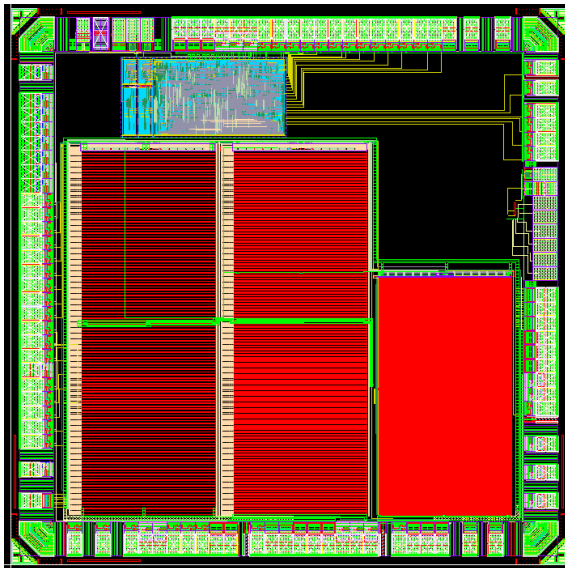
The cell has been designed
in three different versions:

- “simple” layout
- with guard rings around transistors
- with both guard rings and interleaving



Interleaved layout

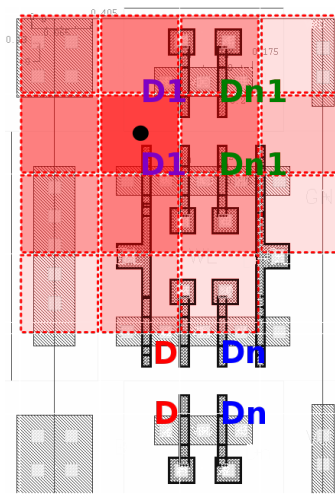
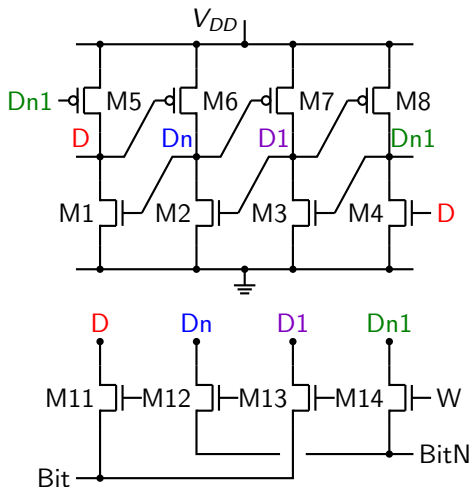
1st test chip: CHIPIX-SRAM-1



Layout:

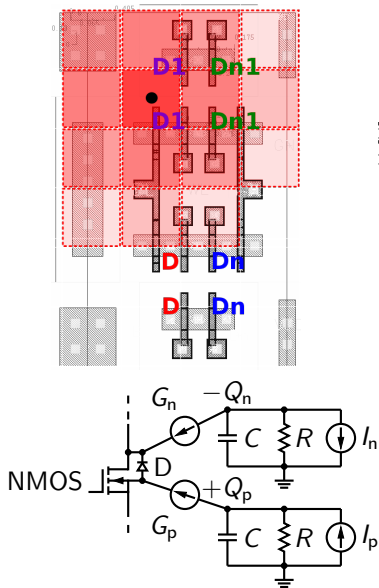
3 256×256 SRAM arrays; SERDES; MOS transistors

DICE Single Event Effect simulation

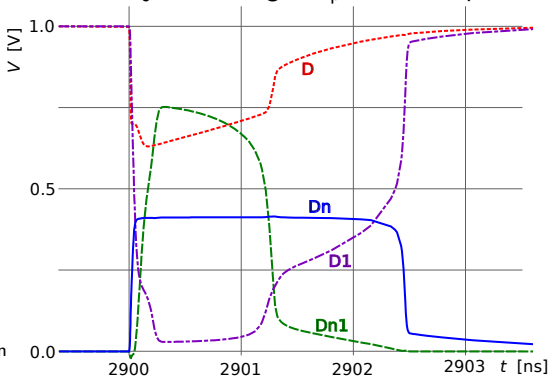


The area affected by a single particle is much larger than a single node!

DICE SEE simulation results



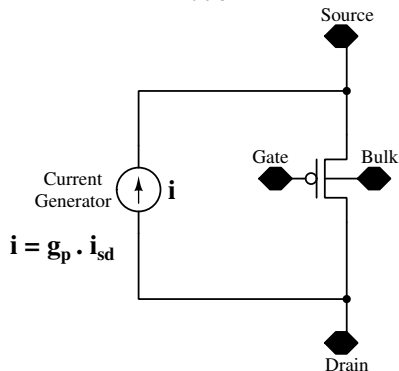
Total injected charge: $Q_p = Q_n = 1 \text{ pC}$



After a 2.5 ns transient, the DICE memory
reverts back to the correct value

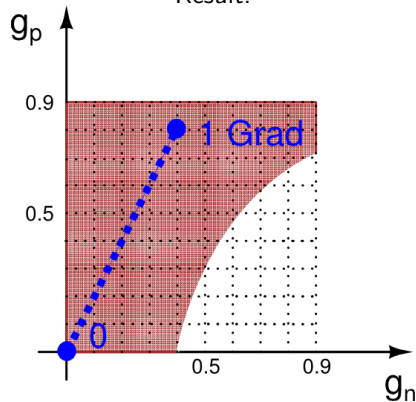
Total Dose simulation

Model:



The parameter g_p (g_n) accounts for the degradation of the PMOS (NMOS) transistor

Result:



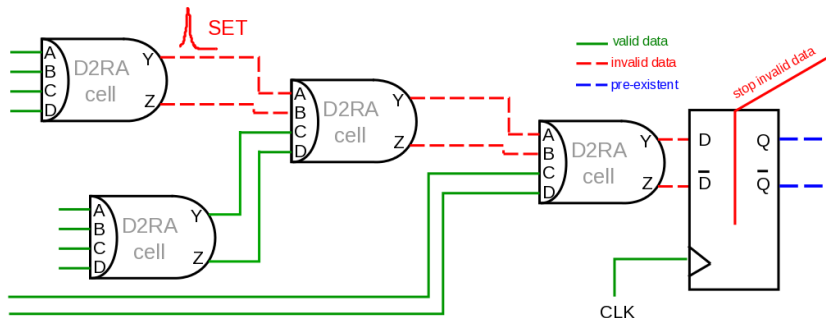
The DICE SRAM is less sensitive to PMOS conductance degradation

D2RA: Double-Rail Redundant Approach

Redundant logic which processes both the bit and the inverted bit

(01) and (10): valid data

(00) and (11): invalid data (Single Event Transient)



V. Ciriani, L. Frontini, V. Liberali, S. Shojaii, A. Stabile, and G. Trucco,
“Radiation-tolerant standard cell synthesis using double-rail redundant approach,”
in *Proc. of Int. Conf. on Electronics, Circuits and Systems (ICECS)*, Sept. 2014,
<http://dx.doi.org/10.1109/ICECS.2014.7050063>

Combinational logic gates:

- AND / NAND
- OR / NOR (identical to AND / NAND with swapped inputs)
- XOR / XNOR (two identical “half-cells”)
- MUX
- NOT (redundant inverter for single-ended signals)

Sequential logic gates:

- Edge-triggered delay flip-flop (D-FF)
- Clock edge detector

D2RA: Logic Constraints

Fully CMOS logic $\rightarrow$ inverting logic gates

Correct points:

input valid data must give (1, 0) or (0, 1) at the outputs

Faulty points: Invalid data are represented by don't cares (-), which can be either (0, 0) or (1, 1)

Gravity points: 0000 and 1111 at the inputs must give (1, 1) and (0, 0) at the outputs, respectively

CD \ AB	AB			
	00	01	11	10
00	1	-	-	-
01	-	0	-	0
11	-	-	0	-
10	-	0	-	1

AND

CD \ AB	AB			
	00	01	11	10
00	1	-	-	-
01	-	1	-	1
11	-	-	0	-
10	-	1	-	0

NAND

Synthesis of a 2-input D2RA AND-NAND

- For both gravity points find the square covers that include neighborhood
- Remaining don't care are filled with ones
- Find minimum covers

AB \ CD	00	01	11	10
00	1	1	1	1
01	1	0	0	0
11	1	0	0	0
10	1	0	0	1

AND - Z output

AB \ CD	00	01	11	10
00	1	1	1	1
01	1	1	0	1
11	1	0	0	0
10	1	1	0	0

NAND - Y output

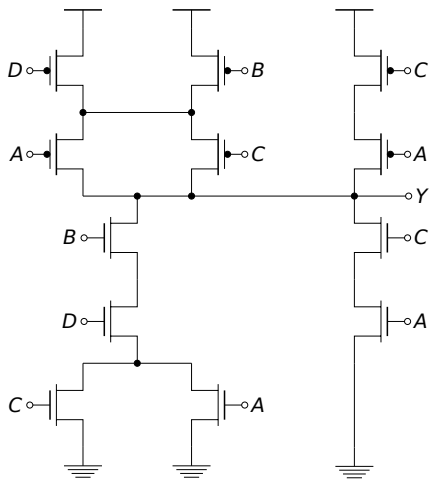
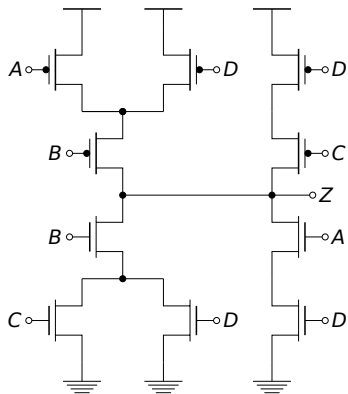
AB \ CD	00	01	11	10
00	1	1	1	1
01	1	0	0	0
11	1	0	0	0
10	1	0	0	1

NAND - Z output

AB \ CD	00	01	11	10
00	1	1	1	1
01	1	1	0	1
11	1	0	0	0
10	1	1	0	0

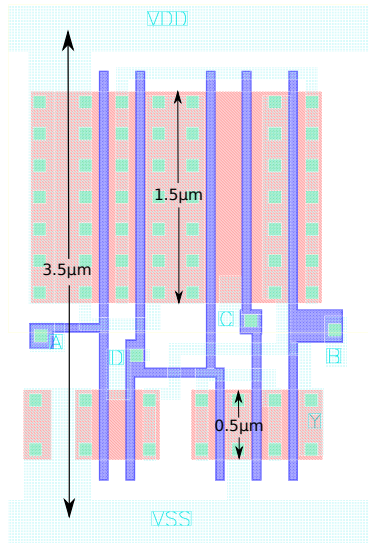
AND - Y output

Schematic of a 2-input D2RA AND-NAND

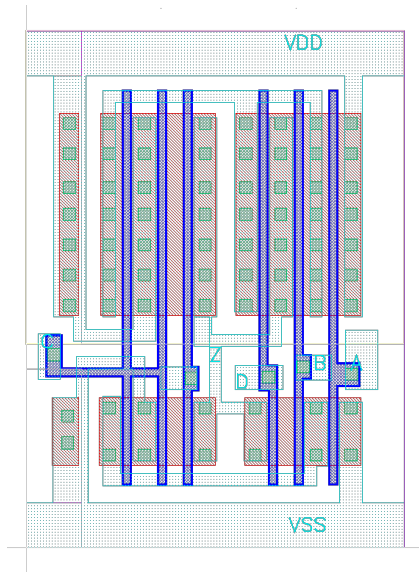
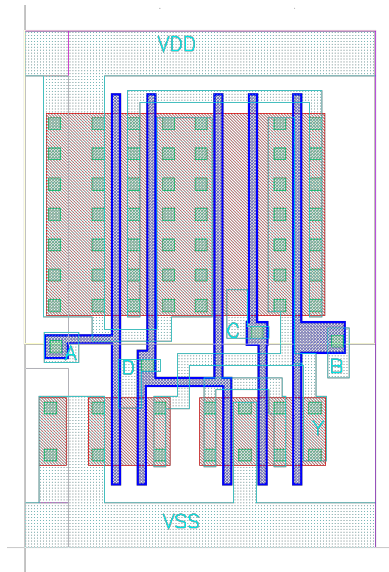


Layout approach for Standard Cells

- To reduce loss of transconductance at 10 MGy, transistors width is not minimum:
 $W_{\text{pmos}} = 1.5\ \mu\text{m}$
 $W_{\text{nmos}} = 0.5\ \mu\text{m}$
- Fixed cell height
- Power supply and ground nets at top and bottom of cells

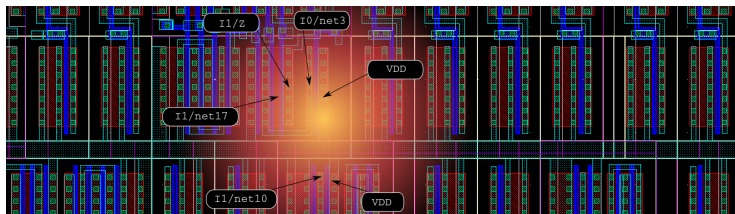


D2RA AND / NAND layout

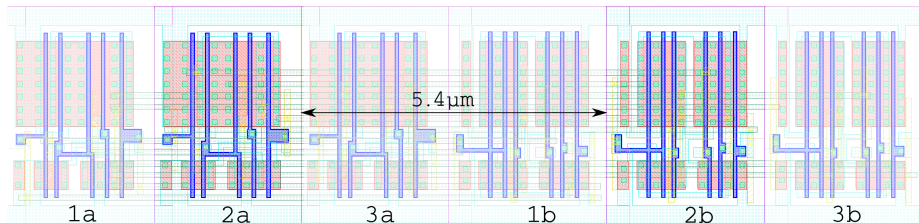


SET effect mitigation

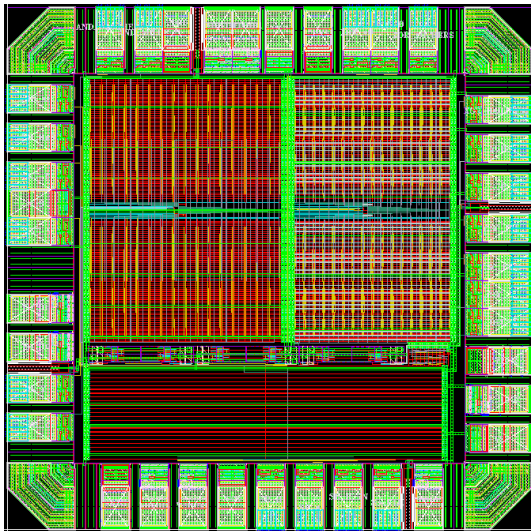
When radiation hits a circuit, the generated charge can affect several nodes causing SETs.



The two parts of a D2RA cell must be placed at a minimum distance of 5 μm :



2nd test chip: CHIPIX-D2RA-2



Layout:

AND/NAND and XOR/XNOR trees; shift register; ring oscillator
all designed with D2RA cells

Purpose:

The **HVR_CCPD** project aims at prototyping an active **CCPD (Capacitively Coupled Pixel Detector)** by developing, testing and characterizing an **HV/HR (High-Voltage/High-Resistivity) CMOS** design and its integration with a pixel detector chip for readout.

Initially the readout chip will be the ATLAS FE-I4 and will be then moved to the RD53 design, when this will become available.

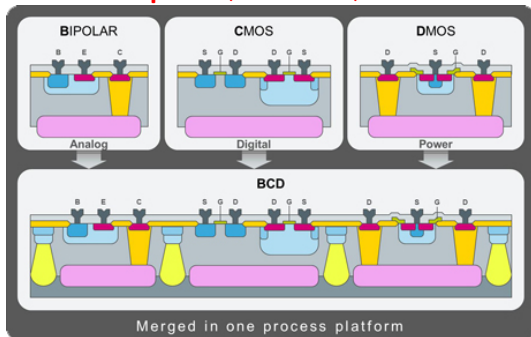
Units: INFN sections of Milano, Genova, Bologna.

Project coordinator: Attilio Andreazza (Milano).

The Project involves electronic designers of three INFN Sections, with expertise in design of rad-hard electronics, and in manufacturing and operating silicon detectors.

BCD8 Technology (STMicroelectronics)

BCD = Bipolar + CMOS + DMOS



	HIGH DENSITY	HIGH VOLTAGE
0.32μm	BCD6s 20/45/70/100V	BCD6s-Offline 800V BCD6s-SOI 100/190V
0.16μm	BCD8s 8/20/40/70V BCD8sP 8/18/25/42V	BCD8s-SOI 300V
0.11μm	BCD9s 20/40/65V	
90nm	BCD10	
Timeline	AVAILABLE	
	IN DEVELOPMENT	

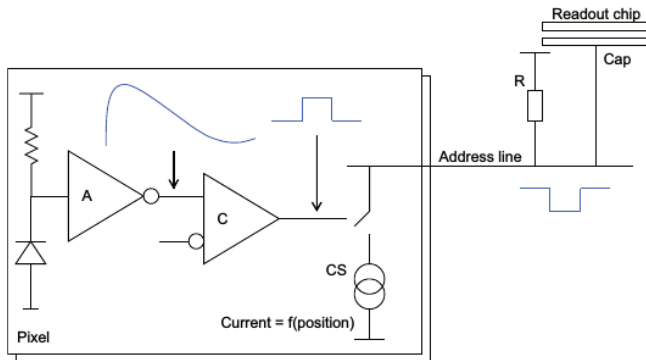
http://www.st.com/web/en/about_st/bcd.html

D. Riccardi, A. Causio, I. Filippi, A. Paleari, L. Vecchi, A. Pregolato, P. Galbiati, C. Contiero, **BCD8 from 7V to 70V: a new 0.18 μm technology platform to address the evolution of applications towards smart power ICs with high logic contents**, in *Proc. 19th Int. Symp. Power Semiconductor Devices & ICs*, 2007. <http://dx.doi.org/10.1109/ISPSD.2007.4294935>

R. Roggero, G. Croce, P. Gattari, E. Castellana, A. Molfese, G. Marchesi, L. Atzeni, C. Buran, A. Paleari, G. Ballarin, S. Manzini, F. Alagi, G. Pizzo, **BCD8sP: An advanced 0.16 μm technology platform with state of the art power devices**, in *Proc. 25th Int. Symp. Power Semiconductor Devices & ICs*, 2013. <http://dx.doi.org/10.1109/ISPSD.2013.6694422>

Chip Design in BCD8

Front-end circuit based on the solution proposed by Ivan Perić et al.:



I. Perić, et al., **High-voltage pixel sensors for ATLAS upgrade**, *Nuclear Instruments and Methods in Physics Research A* (2014), in press.
<http://dx.doi.org/10.1016/j.nima.2014.06.035>

I. Perić, C. Kreidl, P. Fischer, **Particle pixel detectors in high-voltage CMOS technology – New achievements**, *Nuclear Instruments and Methods in Physics Research A* **650** (2011) 158–162.
<http://dx.doi.org/10.1016/j.nima.2010.11.090>

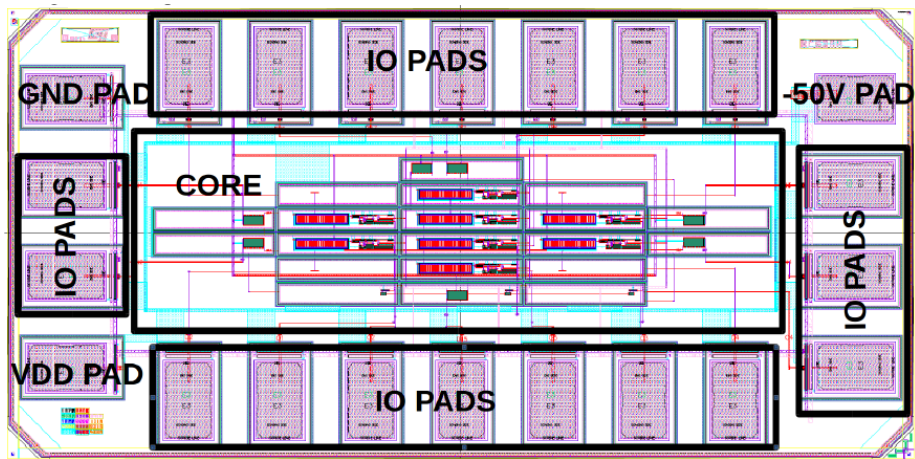
Preliminary Test Chip in BCD8

A preliminary test chip with simple structures was designed in a short time (3 weeks), to test some basic structures:

- passive diodes
- front-end amplifier
- isolation structures (for substrate bias at -50 V)
- ESD protection for signal pads

The “first” demonstrator in BCD8 will be designed in June 2015 (possibly compliant with the CPIX requirements).

Chip Layout



Chip size: 2 mm $\times$ 1 mm

Layout of the Array

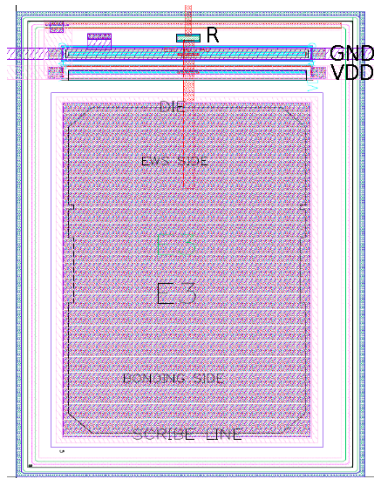
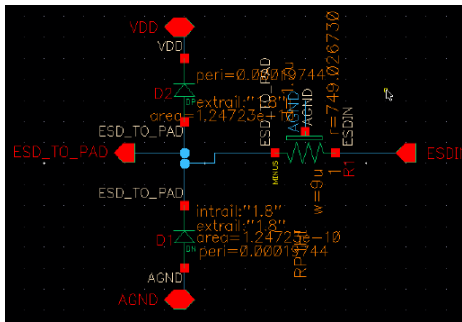


4 Passive pixels (buried N-well to substrate diodes)

8 Active pixels (with the amplifier inside)

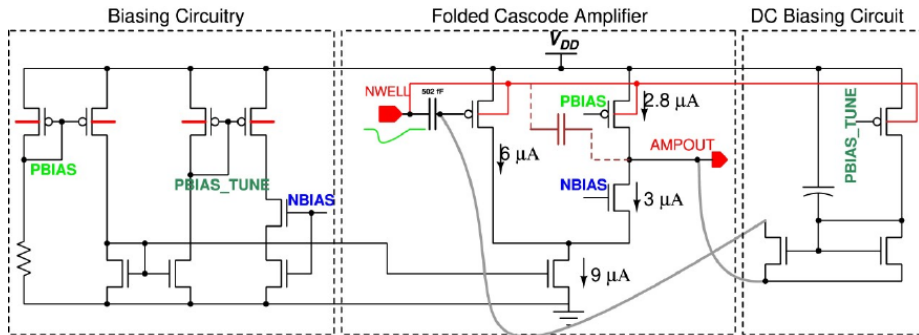
Pixel size: $250\ \mu\text{m} \times 50\ \mu\text{m}$

Layout of an I/O Cell

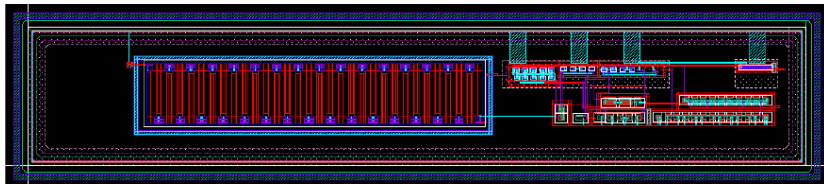


Shielded I/O pad with two protection diodes (towards VDD and GND) and series resistance ($750\ \Omega$) in high-resistivity polysilicon

Amplifier schematic diagram

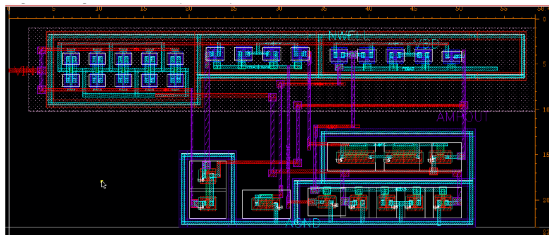


Layout of a single pixel



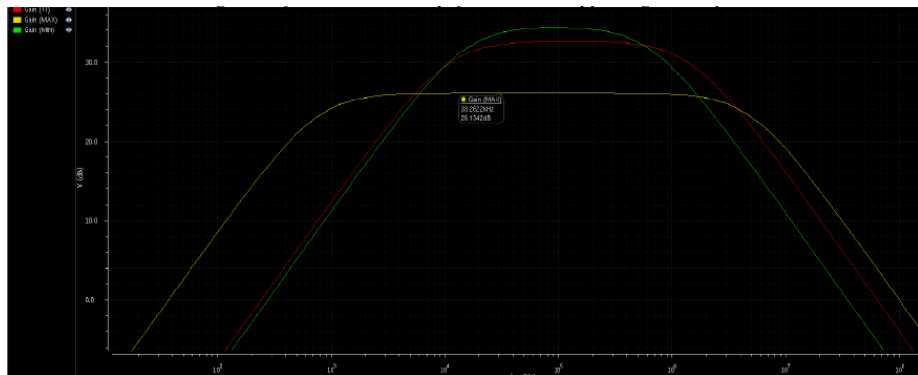
Size: $250\ \mu\text{m} \times 50\ \mu\text{m}$

Left: $0.5\ \text{pF}$ capacitance; Right: amplifier + output buffer



Detail of the folded cascode amplifier

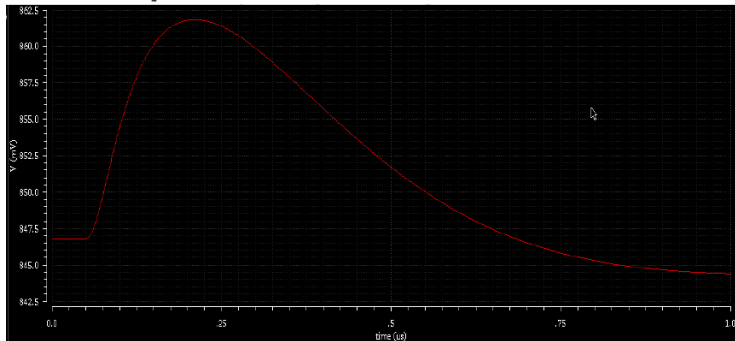
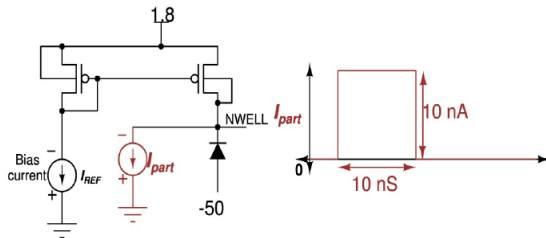
Simulation results: Amplifier gain



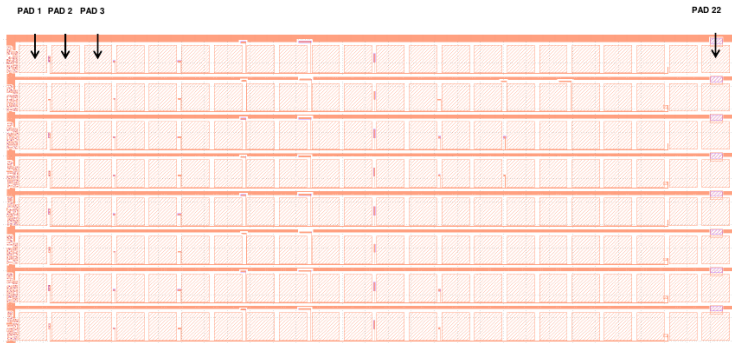
Gain: 26 dB ÷ 34 dB

Bandwidth: from 10 kHz to 1 MHz

Simulation results: Amplifier output



KC01: MOS Test Structures



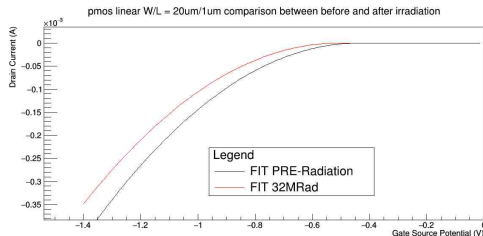
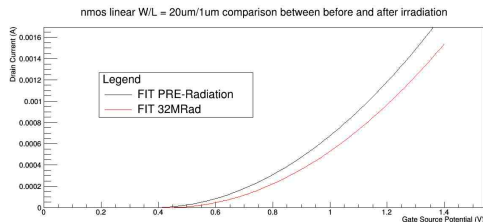
Each row contains single MOS transistors: 1.8 V / 5 V, NMOS / PMOS, standard / ELT

$W/L = 10 \mu\text{m}/1 \mu\text{m}, 20 \mu\text{m}/1 \mu\text{m}, 40 \mu\text{m}/1 \mu\text{m}, 100 \mu\text{m}/1 \mu\text{m}$

Radiation test on KC01

LNS, Catania – May 17-20

TID: 32 Mrad



NMOS

$W/L = 20 \mu\text{m} / 1 \mu\text{m}$

black: TID = 0

red: TID = 32 Mrad

Threshold variation:

$\Delta V_{th}/V_{th} = +20 \%$

Conductance variation:

$\Delta K/K = -7 \%$

PMOS

$W/L = 20 \mu\text{m} / 1 \mu\text{m}$

black: TID = 0

red: TID = 32 Mrad

Threshold variation:

$\Delta V_{th}/V_{th} = +16 \%$

Conductance variation:

$\Delta K/K = -4 \%$

Conclusion

- CHIPIX65: DICE SRAM available for test
- CHIPIX65: D2RA new rad-hard logic family; test chip designed and submitted
- HVR_CCPD: KC53A submitted; 3-month delay in prototype delivery

Future activities:

- Design first chip in BCD8
- Laboratory characterization and radiation test of prototypes (CHPIX65 and HVR_CCPD)
- Study of combined TID/SEE effects in 65 nm
- Study radiation effects in BCD8
- Improvement of models for radiation simulation at circuit level
- Develop a methodology for radiation hardness verification at layout level